

IEEE SW Test Workshop Semiconductor Wafer Test Workshop

> June 7-10, 2009 San Diego, CA

The UltraSound CLEANERTM

« A nondestructive cleaning solution for PC, optimizing test floor yield and COO »





The UltraSound CLEANER™

« A nondestructive cleaning solution for PC, optimizing test floor yield and COO »

Introduction and background
Objectives and goals
1st Process samples before-after
Relevant findings, results and key data
3 years real production data
Summary and conclusion
SWTW questions



Project partners

✓ <u>ST Rousset EWS</u> – EWS Production – <u>1st Prototype</u> Jean-Pierre Rabouin/Robert Diperi/Didier Baumann

✓ <u>ST Grenoble EWS Technology Center</u> – R&D – <u>USC1</u> Pierre Ballet

✓ <u>ST FEM EWS Europe</u> – Pre project Géraldine Thiery

✓ <u>CEPRIM TECHNOLOGIES</u> – Project owner Roland Boyer

✓ <u>GLOBAL TECHNOLOGIES</u> – Automation Franck Pouch

✓ <u>SEMI CONSULTING</u> – Sales/Marketing/Service coordinator Hervé Alle



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Introduction and background

• Probe cards technologies is a key factor for end users operation and the cleaning process could have a huge impact on their productivity – Latest technologies are requiring specific cares,

• Existing off-line tools set are either fully manual, chemical dependant, costly and hazardous solutions,

• In-line ones are modifying the tips geometry and impacting the contacts resistance (CRES),





 In any case, most standard cleaning solutions are mechanically contacting the probe tips.





Objectives and goals

• "Provide me with an alternative solution that has the fastest, most safely and fully automated process control",

• "This industry is requiring a nondestructive solution of cleaning compatible with all types of probe cards without modifying the tips geometry nor impacting the CRES",

• "All types of residues should be removed and ideally probe tips should be reshaped with a contactless process",

• "I need a duplicable and productive solution of cleaning that avoid manual contact during clean".



000111 20KV X300 100um







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Objectives and goals

















- Few mins process only
- Contactless & non destructive solution
- Easy operation
- Automated controls
- Duplicable process
- Cleaner/Reshaper
- All probe cards type compatible
 - Environment free
 - Fast ROI



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Ultrasounds chemistry – Different materials





Process set-up – Probe tips re-pointing





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1st Process samples before/after



All Probe cards impurities are removed within less than 5 minutes



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Before/After Scrubbing

Process set-up Probe tips reshaping



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Even 2µm size particles are removed



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Before/After 90 sec. USC1 Cleaning/Reshaping/Drying

Mesures de répétabilité

25.0000 A40 A39 A38 × A37 × A36 Test die without clean A35 + A34 A33 A32 A31 X A27 A26 A30 A29 A28 **CRES** A21 A25 A24 A23 A22 . 20.0000 . • A17 + A16 A20 × A19 * A18 A15 - A14 ♦ A13 A12 A11 Flat Tip Probe CRES on Al-pads Résistance de contact (ohm) 00000151 Test Die without Clean × A10 ж А9 A8 + A7 A6 15.00 - A5 🔸 A4 🛛 🗧 A3 🔺 A2 🗙 A1 12.50 10.00 CRES (ohms) 7.50 5.00 5.0000 2 50 0.00 0.0000 400 500 0 100 200 300 0 2 6 8 10 12 14 16 18 20 Total TDs at 2-mils of Overtravel

40 tip probe/100 cleans CRES with USC1



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3 years real production data



Summary and conclusion









<u>Preparation for clean</u> - probe card - holder - Z work





- <u>Cleaning step</u>
- manual start
- ultrasound process
- adjustable reshape
- adjustable timing









- <u>Drying step</u>
- air spray
- manual start
- adjustable timing

Back to production

- within 5 mins
- easy operation
- free maintenance
- clean room designed



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Summary and conclusion

5 mins total process

Contactless

Non destructive solution

Easy operation

Automated controls

Duplicable process

Cleaner/Reshaper

All probe cards

Environment free

Yield increased

Probe cards COO

• "Provide me with an alternative solution that has the fastest, most safely and fully automated process control",

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Acknowledgement

Special Thanks to:

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✓ <u>ST Grenoble EWS Technology Center</u>
✓ <u>ST FEM EWS Europe</u>





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Hervé ALLE Managing Director

